ABSTRACT

The present invention discloses a furnace tube for thin film deposition, comprising: a process tube; a wafer boat, arranged inside the process tube and provided with multi-layered supporting members along the length direction of the process tube; a gas supply tube, arranged inside the process tube and provided with multi-layered gas supply holes along the length direction of the process tube. Multi-layered exhaust holes are arranged on the sidewall of the process tube along the length direction, wherein the distribution area of the gas supply holes is gradually reduced from top to bottom along the length direction of the sidewall of the process tube, and the distribution area of the exhaust holes is gradually reduced from top to bottom along the length direction of the sidewall of the process tube. The present invention makes the distribution area of the gas supply holes gradually reduced from top to bottom along the length direction of the sidewall of the process tube and the distribution area of the exhaust holes gradually reduced from top to bottom along the length direction of the sidewall of the process tube by providing multi-layered gas supply holes and multi-layered exhaust holes, so that the gas supply amount of gas supply holes of each layer is the same, and the gas exhaust amount of exhaust holes of each layer is the same, thereby ensuring the uniformity of the thin film deposited on the substrate of each layer consistent.